

























UNIFORMITY OF GATE FILM

	MEAN THICKNESS (nm)	σ
RPN of Si O ₂ (Dry)	1.74	0.287
RPN of Si O ₂ (Wet)	1.68	0.115
RTNO	1.70	0.0293
RTNO +RPN@ 550°C	1.74	0.0246
RTNO +RPN@ 750°C	1.73	0.0296

FIG. 7

